



Nophenol 922[®]

Nophenol 922[®] is an organic based photoresist remover formulated to remove positive and negative photoresist and other organic compounds to provide an ultra clean surface is required.

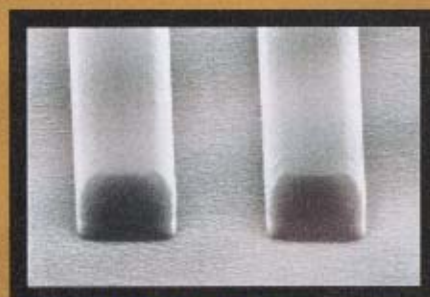
Nophenol 922[®] offers the following advantages

- No Phenol or Chlorinated Solvents
- Extended Bath Life
- Compatible with III to V Compound Semiconductors (ie. GaAs, InP and SiGe)
- Safe to use on Semi-Cured Polyimides
- Compatible with Conventional Semiconductor Materials

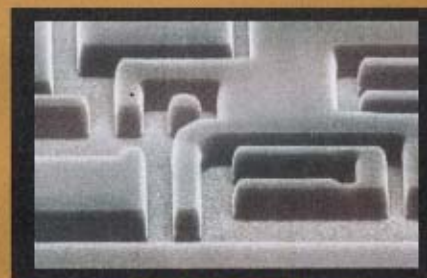
Typical Applications for Nophenol 922[®]

Bulk Photoresist Removal

- MEMS
- Backlap Process
- Chrome Photomasks
- Metal Carriers
- Ink Dot Removal
- Integrated Circuits
- Hybrid Device
- III - V Compound Semiconductors
- Spinner Parts



After ETCH



After ETCH



Nophenol 922[®] /85°C/30min



Nophenol 922[®] /85°C/15min

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